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| APPLICANT'S ART CITATION (Use several sheets if necessary) | | Application To Be Assigned | | | | OFGS File No. P/1071-985 | |
| | | Applicant Takahiro OGUCHI | | | | | |
| | | Filing Date Herewith 4-13-00 | | | | Group Art Unit ---- 2823 | |
| U.S. PATENT DOCUMENTS | | | | | | | |
| Examiner Initial | Document Number | | | | | | Date |
| | | | | | | | Name |
| | | | | | | | Class |
| | | | | | | | Sub-class |
| | | | | | | | Filing Date If Appropriate |
| FOREIGN PATENT DOCUMENTS | | | | | | | |
| | Document Number | | | | | | Date |
| | Country | | | | | | Class |
| | Sub-class | | | | | | Translation |
| | | | | | | | Yes |
| | | | | | | | No |
| | | | | | | | |
| | | | | | | | |
| OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) | | | | | | | |
| JAG | Fujiwara, et al. "Charge accumulation effects on profile distortion in ECR plasma etching", Plasma Sources Sci. Technol. 5 (1996), pages 126-131. | | | | | | |
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| Examiner Joanne A. Garcia | Date Considered May 4, 2002 | | | | | | |
| <small>EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.</small> | | | | | | | |